

L Number	Hits	Search Text	DB	Time stamp
1	434086	photoresist photo-resist photosensitive photo-sensitive (sensitive near (radiation energy photo light))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/01/09 18:16
2	0	(photoresist photo-resist photosensitive photo-sensitive (sensitive near (radiation energy photo light))) same cavity same (expos\$3 irradiat\$5) same develop\$5 same laminat\$5 same membrane	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/01/09 18:17
4	151747	(cover membrane) near2 (layer film coating)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/01/09 18:27
5	13	(photoresist photo-resist photosensitive photo-sensitive (sensitive near (radiation energy photo light))) same (cavity channel microchannel micro-channel well microwell micro-well chamber) same laminat\$5 same membrane	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/01/09 18:21
6	4909745	(cavity channel microchannel micro-channel well microwell micro-well chamber)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/01/09 18:22
7	7959	(laminat\$5 cover\$3) with ((cover membrane) near2 (layer film coating)) with ((cavity channel microchannel micro-channel well microwell micro-well chamber) )	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/01/09 18:27
8	345	(photoresist photo-resist photosensitive photo-sensitive (sensitive near (radiation energy photo light))) same ((laminat\$5 cover\$3) with ((cover membrane) near2 (layer film coating)) with ((cavity channel microchannel micro-channel well microwell micro-well chamber) ) )	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/01/09 18:24
9	35	((photoresist photo-resist photosensitive photo-sensitive (sensitive near (radiation energy photo light))) same ((laminat\$5 cover\$3) with ((cover membrane) near2 (layer film coating)) with ((cavity channel microchannel micro-channel well microwell micro-well chamber) ) ) and (430/\$.cccls. 264/\$.cccls. 204/\$.cccls. 205/\$.cccls.)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/01/09 18:24
10	4826	(laminat\$5 cover\$3) with membrane with ((cavity channel microchannel micro-channel well microwell micro-well chamber) )	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/01/09 18:28
11	1810	(microfluid\$3 micro-fluid\$3 micro adj fluid\$3) adj device	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/01/09 18:28
12	46	((laminat\$5 cover\$3) with membrane with ((cavity channel microchannel micro-channel well microwell micro-well chamber) ) ) and ((microfluid\$3 micro-fluid\$3 micro adj fluid\$3) adj device )	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/01/09 18:30
15	21	(photoresist photo-resist photosensitive photo-sensitive (sensitive near (radiation energy photo light))) same ((laminat\$5 cover\$3) with membrane with ((cavity channel microchannel micro-channel well microwell micro-well chamber) ) )	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/01/09 18:33
16	9468	(photoresist photo-resist photosensitive photo-sensitive (sensitive near (radiation energy photo light))) near first:	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/01/09 18:33

17	8493	(photoresist photo-resist photosensitive photo-sensitive (sensitive near (radiation energy photo light))) near second!	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/01/09 18:33
19	35491	photomask photo-mask photo adj mask	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/01/09 18:34
22	30876	(electrode gate opaque shield\$3) near2 mask	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/01/09 18:36
23	10	((photoresist photo-resist photosensitive photo-sensitive (sensitive near (radiation energy photo light))) near first!) same ((photoresist photo-resist photosensitive photo-sensitive (sensitive near (radiation energy photo light))) near second!) same (photomask photo-mask photo adj mask) same ((electrode gate opaque shield\$3) near2 mask)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/01/09 18:37
24	270	(photoresist photo-resist photosensitive photo-sensitive (sensitive near (radiation energy photo light))) same (photomask photo-mask photo adj mask) same ((electrode gate opaque shield\$3) near2 mask)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/01/09 18:37
25	59	((photoresist photo-resist photosensitive photo-sensitive (sensitive near (radiation energy photo light))) same (photomask photo-mask photo adj mask) same ((electrode gate opaque shield\$3) near2 mask)) same ((cavity channel microchannel micro-channel well microwell micro-well chamber) )	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/01/09 18:41
26	699	((photoresist photo-resist photosensitive photo-sensitive (sensitive near (radiation energy photo light))) near first!) with ((cavity channel microchannel micro-channel well microwell micro-well chamber) )	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/01/09 18:41
27	741	((photoresist photo-resist photosensitive photo-sensitive (sensitive near (radiation energy photo light))) near second!) with ((cavity channel microchannel micro-channel well microwell micro-well chamber) )	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/01/09 18:41
28	18764	(electrochemical electro-chemical electro adj chemical) adj cell	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/01/09 18:41
29	0	((photoresist photo-resist photosensitive photo-sensitive (sensitive near (radiation energy photo light))) near first!) with ((cavity channel microchannel micro-channel well microwell micro-well chamber) ) same ((photoresist photo-resist photosensitive photo-sensitive (sensitive near (radiation energy photo light))) near second!) with ((cavity channel microchannel micro-channel well microwell micro-well chamber) ) same (photomask photo-mask photo adj mask) same ((electrode gate opaque shield\$3) near2 mask)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/01/09 18:42

31	37	((microfluid\$3 micro-fluid\$3 micro adj fluid\$3) adj device ) ((electrochemical electro-chemical electro adj chemical) adj cell)) and ((photoresist photo-resist photosensitive photo-sensitive (sensitive near (radiation energy photo light))) near first!) and ((photoresist photo-resist photosensitive photo-sensitive (sensitive near (radiation energy photo light))) near second!) and ((cavity channel microchannel micro-channel wall microwell micro-well chamber) )	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/01/09 18:45
32	86	((photoresist photo-resist photosensitive photo-sensitive (sensitive near (radiation energy photo light))) near first!) near4 (photomask photo-mask photo adj mask)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/01/09 18:45
33	126	((photoresist photo-resist photosensitive photo-sensitive (sensitive near (radiation energy photo light))) near second!) near4 ((electrode gate opaque shield\$3) near2 mask) near2 mask)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/01/09 18:46
34	0	((photoresist photo-resist photosensitive photo-sensitive (sensitive near (radiation energy photo light))) near first!) near4 (photomask photo-mask photo adj mask)) with ((photoresist photo-resist photosensitive photo-sensitive (sensitive near (radiation energy photo light))) near second!) near4 ((electrode gate opaque shield\$3) near2 mask)) with (single near4 (expos\$3 irradiat\$5))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/01/09 18:46
35	0	((photoresist photo-resist photosensitive photo-sensitive (sensitive near (radiation energy photo light))) near first!) near4 (photomask photo-mask photo adj mask)) same ((photoresist photo-resist photosensitive photo-sensitive (sensitive near (radiation energy photo light))) near second!) near4 ((electrode gate opaque shield\$3) near2 mask)) same (single near4 (expos\$3 irradiat\$5))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/01/09 18:48
36	0	((photoresist photo-resist photosensitive photo-sensitive (sensitive near (radiation energy photo light))) near first!) near4 (photomask photo-mask photo adj mask)) same ((photoresist photo-resist photosensitive photo-sensitive (sensitive near (radiation energy photo light))) near second!) near4 ((electrode gate opaque shield\$3) near2 mask)) same (one near4 (expos\$3 irradiat\$5))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/01/09 18:47
37	0	((photoresist photo-resist photosensitive photo-sensitive (sensitive near (radiation energy photo light))) near first!) near4 (photomask photo-mask photo adj mask)) same ((photoresist photo-resist photosensitive photo-sensitive (sensitive near (radiation energy photo light))) near second!) near4 ((electrode gate opaque shield\$3) near2 mask))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/01/09 18:47
38	10	((photoresist photo-resist photosensitive photo-sensitive (sensitive near (radiation energy photo light))) near first!) same (photomask photo-mask photo adj mask) same ((photoresist photo-resist photosensitive photo-sensitive (sensitive near (radiation energy photo light))) near second!) same ((electrode gate opaque shield\$3) near2 mask)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/01/09 18:47

39	124196	{single one }near4 {expos\$3 irradiat\$5}	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/01/09 18:49
40	12	{photomask photo-mask photo adj mask} same {electrode gate opaque shield\$3} near2 mask} same {(single one }near4 {expos\$3 irradiat\$5)}	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/01/09 18:53
41	40	{photomask photo-mask photo adj mask} with cover\$3 with {(electrode gate opaque shield\$3} near2 mask}	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/01/09 18:51
42	710	{back-side backside back adj side} adj {expos\$3 irradiat\$5}	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/01/09 18:52
43	734	{photomask photo-mask photo adj mask} same {electrode gate opaque shield\$3} near2 mask}	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/01/09 18:53
44	5	{photomask photo-mask photo adj mask} same {(electrode gate opaque shield\$3} near2 mask} ) same {(back-side backside back adj side} adj {expos\$3 irradiat\$5} )	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/01/09 18:54
46	1	{back-side backside back adj side} adj {expos\$3 irradiat\$5} ) and 430/395.ccls.	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/01/09 18:54
-	60	MADOU-M-.in. MADOU-MARC-.in. MADOU-MARC-J-.in. MADOU-MARK-J-.in. MADOU-M-J-.in.	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/01/09 15:33
-	71108	resist photoresist photo-resist photosensitive photo-sensitive (sensitive near (photo light energy radiation))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/01/09 17:54
-	11	{MADOU-M-.in. MADOU-MARC-.in. MADOU-MARC-J-.in. MADOU-MARK-J-.in. MADOU-M-J-.in. } and (resist photoresist photo-resist photosensitive photo-sensitive (sensitive near (photo light energy radiation)))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/01/09 15:45
-	1810	{microfluid\$3 micro-fluid\$3 micro adj fluid\$3} adj device	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/01/09 18:28
-	4	((("4874500") or ("4900405"))).PN.	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/01/09 15:46
-	421	(resist photoresist photo-resist photosensitive photo-sensitive (sensitive near (photo light energy radiation))) and {microfluid\$3 micro-fluid\$3 micro adj fluid\$3} adj device }	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/01/09 15:48
-	34233	{resist photoresist photo-resist photosensitive photo-sensitive (sensitive near (photo light energy radiation))) with negative	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/01/09 15:48
-	75	{microfluid\$3 micro-fluid\$3 micro adj fluid\$3} adj device } and {(resist photoresist photo-resist photosensitive photo-sensitive (sensitive near (photo light energy radiation))) with negative}	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/01/09 15:49
-	96841	electrochemical electro-chemical electro adj chemical	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/01/09 15:52

	0	{{(resist photoresist photo-resist photosensitive photo-sensitive (sensitive near (photo light energy radiation))) with negative) same (cavity chamber)) same (laminat\$5) with membrane}	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/01/09 16:07
	1153	liga!	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/01/09 15:54
	105	((microfluid\$3 micro-fluid\$3 micro adj fluid\$3) adj device ) and liga!	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/01/09 15:59
	68	liga! and 430/\$.cols.	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/01/09 16:09
	4964576	channel microchannel micro-channel cavity chamber void well	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/01/09 16:28
	59543	(resist photoresist photo-resist photosensitive photo-sensitive (sensitive near (photo light energy radiation))) with (channel microchannel micro-channel cavity chamber void well)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/01/09 16:33
	21	{{(resist photoresist photo-resist photosensitive photo-sensitive (sensitive near (photo light energy radiation))) with (channel microchannel micro-channel cavity chamber void well)) with cover\$3 with membrane	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/01/09 16:33
	202	{{(resist photoresist photo-resist photosensitive photo-sensitive (sensitive near (photo light energy radiation))) with (channel microchannel micro-channel cavity chamber void well)) and ((microfluid\$3 micro-fluid\$3 micro adj fluid\$3) adj device )	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/01/09 16:35
	5499	(resist photoresist photo-resist photosensitive photo-sensitive (sensitive near (photo light energy radiation))) with (channel microchannel micro-channel cavity chamber void well) with (cover\$3 membrane laminat\$5)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/01/09 16:34
	36	((resist photoresist photo-resist photosensitive photo-sensitive (sensitive near (photo light energy radiation))) with (channel microchannel micro-channel cavity chamber void well) with (cover\$3 membrane laminat\$5)) and ((microfluid\$3 micro-fluid\$3 micro adj fluid\$3) adj device )	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/01/09 16:42
	309	((microfluid\$3 micro-fluid\$3 micro adj fluid\$3) adj device ) with (method process step) with (form\$3 formation manufactur\$3 produc\$5)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/01/09 16:45
	1	{{(microfluid\$3 micro-fluid\$3 micro adj fluid\$3) adj device ) with (method process step) with (form\$3 formation manufactur\$3 produc\$5)) same ((resist photoresist photo-resist photosensitive (sensitive near (photo light energy radiation))) with negative)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/01/09 16:44
	15	{{(microfluid\$3 micro-fluid\$3 micro adj fluid\$3) adj device ) with (method process step) with (form\$3 formation manufactur\$3 produc\$5)) same (resist photoresist photo-resist photosensitive (sensitive near (photo light energy radiation)))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/01/09 16:47

-	4966878	{resist photoresist photo-resist photosensitive photo-sensitive (sensitive near (photo light energy radiation))) same membrane (channel microchannel micro-channel cavity chamber void well)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/01/09 16:53
-	1160	{resist photoresist photo-resist photosensitive photo-sensitive (sensitive near (photo light energy radiation))) same membrane same (channel microchannel micro-channel cavity chamber void well)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/01/09 16:55
-	86	{(resist photoresist photo-resist photosensitive photo-sensitive (sensitive near (photo light energy radiation))) same membrane same (channel microchannel micro-channel cavity chamber void well)) and 430/\$.cells,	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/01/09 17:08
-	25540	{resist photoresist photo-resist photosensitive photo-sensitive (sensitive near (photo light energy radiation))) near2 first!	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/01/09 17:08
-	20915	{resist photoresist photo-resist photosensitive photo-sensitive (sensitive near (photo light energy radiation))) near2 second!	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/01/09 17:09
-	3150	{back-side back adj side backside) near2 (expos\$3 irradiat\$5)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/01/09 17:11
-	4	{(resist photoresist photo-resist photosensitive photo-sensitive (sensitive near (photo light energy radiation))) near2 first!) same ((resist photoresist photo-resist photosensitive photo-sensitive (sensitive near (photo light energy radiation))) near2 second!) same ((back-side back adj side backside) near2 (expos\$3 irradiat\$5)) same electrode ((resist photoresist photo-resist photosensitive photo-sensitive (sensitive near (photo light energy radiation))) near2 first!) same ((resist photoresist photo-resist photosensitive photo-sensitive (sensitive near (photo light energy radiation))) near2 second!) same ((back-side back adj side backside) near2 (expos\$3 irradiat\$5))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/01/09 17:12
-	18	{(resist photoresist photo-resist photosensitive photo-sensitive (sensitive near (photo light energy radiation))) near2 first!) same ((resist photoresist photo-resist photosensitive photo-sensitive (sensitive near (photo light energy radiation))) near2 second!) same ((back-side back adj side backside) near2 (expos\$3 irradiat\$5))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/01/09 17:15
-	19879	{electrochemical electro-chemical electro adj chemical) near cell	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/01/09 17:16
-	21676	{(microfluid\$3 micro-fluid\$3 micro adj fluid\$3) adj device ) ((electrochemical electro-chemical electro adj chemical) near cell)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/01/09 17:48
-	35491	photomask photo-mask photo adj mask	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/01/09 17:19
-	79461	{membrane cover} near (layer film)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/01/09 17:20

-	0	((microfluid\$3 micro-fluid\$3 micro adj fluid\$3) adj device ) ((electrochemical electro-chemical electro adj chemical) near cell)) and ((resist photoresist photo-resist photosensitive photo-sensitive (sensitive near (photo light energy radiation))) same (photomask photo-mask photo adj mask) same ((membrane cover) near (layer film)) same (channel microchannel micro-channel cavity chamber void well))	USPAT; US-PGPUB; EPO; JPO; DERNMENT	2004/01/09 17:22
-	8	((resist photoresist photo-resist photosensitive photo-sensitive (sensitive near (photo light energy radiation))) same (photomask photo-mask photo adj mask) same ((membrane cover) near (layer film)) same (channel microchannel micro-channel cavity chamber void well))	USPAT; US-PGPUB; EPO; JPO; DERNMENT	2004/01/09 17:24
-	29	((microfluid\$3 micro-fluid\$3 micro adj fluid\$3) adj device ) ((electrochemical electro-chemical electro adj chemical) near cell)) and ((resist photoresist photo-resist photosensitive photo-sensitive (sensitive near (photo light energy radiation))) and (photomask photo-mask photo adj mask) and ((membrane cover) near (layer film)) and (channel microchannel micro-channel cavity chamber void well))	USPAT; US-PGPUB; EPO; JPO; DERNMENT	2004/01/09 17:26
-	28590	((resist photoresist photo-resist photosensitive photo-sensitive (sensitive near (photo light energy radiation))) with (develop\$5 etch\$4 form\$3) with (channel microchannel micro-channel cavity chamber void well))	USPAT; US-PGPUB; EPO; JPO; DERNMENT	2004/01/09 17:51
-	50	((resist photoresist photo-resist photosensitive photo-sensitive (sensitive near (photo light energy radiation))) with (develop\$5 etch\$4 form\$3) with (channel microchannel micro-channel cavity chamber void well)) same (fluid near2 communication)	USPAT; US-PGPUB; EPO; JPO; DERNMENT	2004/01/09 17:54
-	434086	photoresist photo-resist photosensitive photo-sensitive (sensitive near (photo light energy radiation))	USPAT; US-PGPUB; EPO; JPO; DERNMENT	2004/01/09 17:54
-	392389	(channel microchannel micro-channel cavity chamber void well) near2 (two large\$1 small\$2 big\$4)	USPAT; US-PGPUB; EPO; JPO; DERNMENT	2004/01/09 18:02
-	29	((channel microchannel micro-channel cavity chamber void well) near2 (two large\$1 small\$2 big\$4)) same ((resist photoresist photo-resist photosensitive photo-sensitive (sensitive near (photo light energy radiation))) near2 first) same ((resist photoresist photo-resist photosensitive photo-sensitive (sensitive near (photo light energy radiation))) near2 second)	USPAT; US-PGPUB; EPO; JPO; DERNMENT	2004/01/09 18:03